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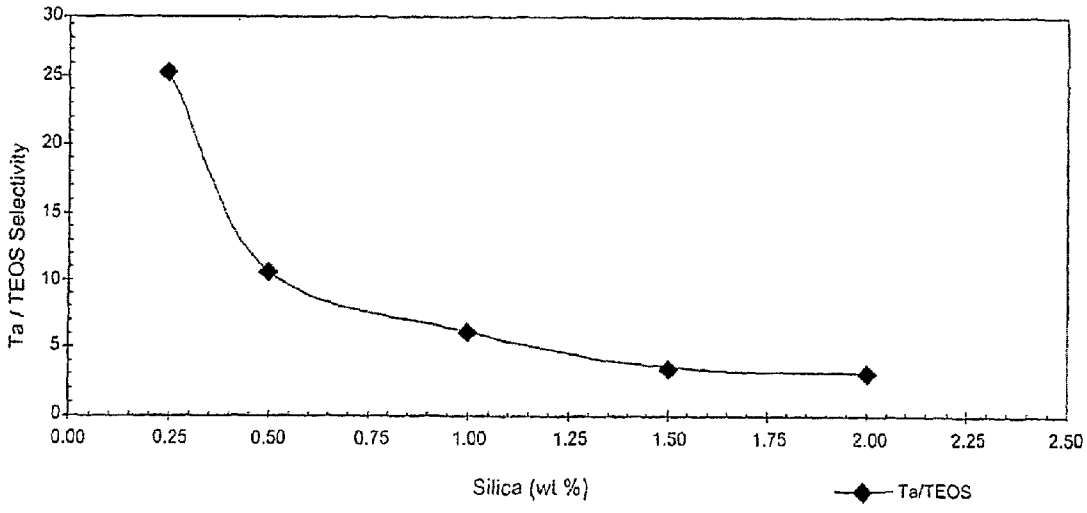
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(54) Title: IODATE-CONTAINING CHEMICAL-MECHANICAL POLISHING COMPOSITIONS AND METHODS



(57) Abstract: The invention provides compositions and methods for planarizing or polishing a substrate. The composition comprises an abrasive, iodate ion, a nitrogen-containing compound selected from the group consisting of a nitrogen-containing C_{4-20} heterocycle and a C_{1-20} alkylamine, and a liquid carrier comprising water.

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